

L8 ANSWER 1 OF 8 USPATFULL  
 AN 97:94039 USPATFULL  
 TI Light-sensitive lithographic printing plate having a light sensitive layer comprising a **clathrate compound**  
 IN Noguchi, Kazuo, Hino, Japan  
 Fukumuro, Kaori, Hino, Japan  
 Matsubara, Shinichi, Hino, Japan  
 Koya, Yoshihiro, Yokohama, Japan  
 Tomiyasu, Hiroshi, Yokohama, Japan  
 Kajiwara, Shigeru, Yokohama, Japan  
 PA Konica Corporation, Tokyo, Japan (non-U.S. corporation)  
 PI US 5677101 19971014  
 AI US 1995-491731 19950619 (8)  
 PRAI JP 1994-162611 19940621  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Chu, John S.  
 LREP Finnegan, Henderson, Farabow, Garrett & Dunner, L.L.P.  
 CLMN Number of Claims: 3  
 ECL Exemplary Claim: 1  
 DRWN No Drawings  
 LN.CNT 1237  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 AB Disclosed is a light-sensitive lithographic printing plate which comprises an aluminum plate having a surface subjected to roughening treatment and then anodization treatment and colored by a solution containing a UV absorber so that at an absorption local maximum wavelength between 340 and 450 nm, reflection optical density DS is higher by 0.02 to 0.5 than that obtained when the surface is not colored, and a positive light-sensitive composition layer containing an o-quinonediazide compound and a clathrate compound provided by coating on the aluminum plate after coloration.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L8 ANSWER 2 OF 8 USPATFULL  
 AN 97:47237 USPATFULL  
 TI Light-sensitive lithographic printing plate utilizing o-quinone diazide light-sensitive layer containing cyclic **clathrate compound**  
 IN Higashino, Katuhiko, Hino, Japan  
 Fukumuro, Kaori, Hino, Japan  
 Matsubara, Shinichi, Hino, Japan  
 Sasaki, Mitsuru, Yokohama, Japan  
 Ohta, Katsuko, Yokohama, Japan  
 Matsuo, Fumiyuki, Yokohama, Japan  
 PA Konica Corporation, Tokyo, Japan (non-U.S. corporation)  
 Mitsubishi Chemical Corporation, Tokyo, Japan (non-U.S. corporation)  
 PI US 5635328 19970603  
 AI US 1994-291197 19940816 (8)  
 PRAI JP 1993-228046 19930821  
 DT Utility  
 FS Granted  
 EXNAM Primary Examiner: Young, Christopher G.  
 LREP Frishauf, Holtz, Goodman, Langer & Chick, P.C.  
 CLMN Number of Claims: 11  
 ECL Exemplary Claim: 1  
 DRWN No Drawings  
 LN.CNT 1364  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 AB Disclosed are a light-sensitive lithographic printing plate which comprises a support subjected to graining treatment and anodization treatment and a layer of a positive light-sensitive composition

containing a o-quinonediazide compound, an alkali-soluble resin and a clathrate compound provided on the support, and a method of processing the same which comprises subjecting the plate to image exposure and then development processing with a developing agent containing an alkali metal silicate.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L8 ANSWER 3 OF 8 USPATFULL

AN 95:3471 USPATFULL

TI Blast media containing surfactant-clathrate compound

IN Winston, Anthony E., East Brunswick, NJ, United States

Yam, Benny S., Holmdel, NJ, United States

Jones, Keith A., Yardley, PA, United States

PA Church & Dwight Co., Inc., Princeton, NJ, United States (U.S. corporation)

PI US 5380347 19950110

AI US 1994-193759 19940203 (8)

RLI Division of Ser. No. US 1993-6659, filed on 21 Jan 1993, now patented, Pat. No. US 5332447

DT Utility

FS Granted

EXNAM Primary Examiner: Dean, Richard O.; Assistant Examiner: El-Arini, Zeinab

LREP Barris, Charles B.

CLMN Number of Claims: 13

ECL Exemplary Claim: 1

DRWN No Drawings

LN.CNT 494

AB A blast media for stripping contaminants from a solid surface comprises abrasive particles and a surfactant in the form of a granular surfactant-clathrate compound formed of a surfactant and a water soluble compound having clathration capability such as urea. The surfactant reduces the amount of water soluble residues which remain on the targeted surface and enhances the removal of dirt, grease and oil from the targeted surface.

L8 ANSWER 4 OF 8 USPATFULL

AN 94:100030 USPATFULL

TI Clathrate compounds comprising tetrakisphenols as host

IN Asai, Makoto, Ichihara, Japan

Suzuki, Hiroshi, Ichihara, Japan

Ichikawa, Takako, Ichihara, Japan

PA Nippon Soda Co., Ltd., Tokyo, Japan (non-U.S. corporation)

PI US 5364977 19941115

AI US 1993-105546 19930812 (8)

RLI Continuation-in-part of Ser. No. US 1993-98290, filed on 4 Aug 1993

PRAI JP 1992-345524 19921201

DT Utility

FS Granted

EXNAM Primary Examiner: Lone, Werren B.

LREP Mason, Jr., Joseph C., Oujevolk, George B., Smith, Ronald E.

CLMN Number of Claims: 11

ECL Exemplary Claim: 1

DRWN 52 Drawing Figure(s); 52 Drawing Page(s)

LN.CNT 991

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB The present invention provides novel clathrate compounds using tetrakisphenols as host. The clathrate compounds are obtained easily and efficiently by reacting tetrakisphenols represented by the general formula [I] as host and various organic compounds such as alcohol, ether, ester, ketone, heterocyclic compounds containing nitrogen, essential oil, perfume and the like as guest under the condition of

solvent-free or diluted with solvent if required. ##STR1## wherein X represents (CH.sub.2)<sub>n</sub>, n represents 0-3, and R.sup.1 and R.sup.2 represents each independently hydrogen atom, a lower alkyl group, a phenyl group optionally having substituents, a halogen atom or a lower alkoxy group.

The clathrate compounds specified in the present invention are useful in the technological field of selective separation, chemical stabilization, conversion to non-volatility, powder processing and the like.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L8 ANSWER 5 OF 8 USPATFULL  
AN 94:68377 USPATFULL  
TI Blast media containing surfactant-**clathrate compound**  
IN Winston, Anthony E., East Brunswick, NJ, United States  
Yam, Benny S., Holmdel, NJ, United States  
Jones, Keith A., Yardley, PA, United States  
PA Church & Dwight Co., Inc., Princeton, NJ, United States (U.S. corporation)  
PI US 5336281 19940809  
AI US 1994-193762 19940203 (8)  
RLI Division of Ser. No. US 1993-6659, filed on 21 Jan 1993  
DT Utility  
FS Granted  
EXNAM Primary Examiner: Bell, Mark L.; Assistant Examiner: Jones, Deborah  
LREP Barris, Charles B.  
CLMN Number of Claims: 15  
ECL Exemplary Claim: 1  
DRWN No Drawings  
LN.CNT 473

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A blast media for stripping contaminants from a solid surface comprises abrasive particles and a surfactant in the form of a granular surfactant-clathrate compound formed of a surfactant and a water soluble compound having clathration capability such as urea. The surfactant reduces the amount of water soluble residues which remain on the targeted surface and enhances the removal of dirt, grease and oil from the targeted surface.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L8 ANSWER 6 OF 8 USPATFULL  
AN 94:64124 USPATFULL  
TI Method of cleaning using a blast media containing a surfactant-**clathrate compound**  
IN Winston, Anthony E., East Brunswick, NJ, United States  
Yam, Benny S., Holmdel, NJ, United States  
Jones, Keith A., Yardley, PA, United States  
PA Church & Dwight Co., Inc., Princeton, NJ, United States (U.S. corporation)  
PI US 5332447 19940726  
AI US 1993-6659 19930121 (8)  
DT Utility  
FS Granted  
EXNAM Primary Examiner: Breneman, R. Bruce; Assistant Examiner: Dunn, Jr., Thomas G.  
LREP Barris, Charles B.  
CLMN Number of Claims: 20  
ECL Exemplary Claim: 1  
DRWN No Drawings  
LN.CNT 487

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A blast media for stripping contaminants from a solid surface comprises

abrasive particles and a surfactant in the form of a granular surfactant-clathrate compound formed of a surfactant and a water soluble compound having clathration capability such as urea. The surfactant reduces the amount of water soluble residues which remain on the targeted surface and enhances the removal of dirt, grease and oil from the targeted surface.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L8 ANSWER 7 OF 8 USPATFULL  
AN 91:12706 USPATFULL  
TI Detergent composition containing clathrate granules of a perfume-clathrate compound  
IN Nebashi, Tutomu, Tochigi, Japan  
Yabe, Shinichi, Tochigi, Japan  
Sai, Fumio, Tochigi, Japan  
Izumi, Yu, Chiba, Japan  
Fujieda, Takashi, Chiba, Japan  
PA Kao Corporation, Tokyo, Japan (non-U.S. corporation)  
PI US 4992198 19910212  
AI US 1989-297842 19890113 (7)  
PRAI JP 1988-9163 19880119  
JP 1988-19254 19880129  
DT Utility  
FS Granted  
EXNAM Primary Examiner: Wax, Robert A.; Assistant Examiner: Steffe, Eric  
LREP Flynn, Thiel, Boutell & Tanis  
CLMN Number of Claims: 12  
ECL Exemplary Claim: 1  
DRWN No Drawings  
LN.CNT 679

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A high density-having, granular, concentrated detergent composition comprises a detergent component(s) and clathrate granules of a perfume-clathrate compound comprising a perfume and a compound having a clathration capability. The clathrate granules have an average size of 100 to 1500 micrometers.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L8 ANSWER 8 OF 8 USPATFULL  
AN 71:32526 USPATFULL  
TI **CLATHRATE COMPOUNDS**  
IN Dosch, Werner, Mainz, Germany, Federal Republic of  
PA Dyckerhoff Zementwerke A.G., Wiesbaden-Amoneburg, Germany, Federal Republic of  
PI US 3607863 19710921  
AI US 1967-619486 19670228 (4)  
DT Utility  
FS Granted  
EXNAM Primary Examiner: Levow, Tobias E.; Assistant Examiner: Scott, Watson T.  
LREP Radde; Erich M., McClure; Charles A., Weiser; Gerard J., Stapler; Alfred  
CLMN Number of Claims: 10  
DRWN 9 Drawing Figure(s); 3 Drawing Page(s)  
LN.CNT 652

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A composition composed of an inorganic carrier material of the formula

$4 \text{ MeO} \cdot \text{sup} \dots \text{X} \cdot \text{sub} \cdot 2 \text{ O} \cdot \text{sub} \cdot 3 \cdot \text{sup} \dots \text{n aq}$

Wherein

Me is an alkaline earth metal,

X is trivalent iron or aluminum,

aq is water of crystallization, and

n is at least 7,

Having adsorbed thereto or included in its crystal lattice a polar organic compound or a nonpolar organic compound and a polar organic compound. Said carrier material may contain anions such as  $\text{SO}_4^{2-}$ ,  $\text{CO}_3^{2-}$ , or  $\text{Cl}^-$  and may be alkylated.

The resulting adsorption complex, inclusion or clathrate compound is stable, of a high degree of crystalline orderliness, and uniform in its physical and chemical properties.

It is prepared by contacting the inorganic carrier material with the liquid or gaseous organic compound or with its solution. It is also obtained by adding the organic compound during preparation of the inorganic carrier material.

The adsorption complexes, inclusion or clathrate compounds are useful for modifying cement and concrete, for storing insecticides, perfumes, drugs, dyes etc. to be released at the site of their use, and for many other technical purposes.

The inorganic carrier material is obtained, for instance, by reacting mono- or tricalcium aluminate or tetracalcium aluminate ferrite with water or calcium hydroxide suspensions or by reacting alkali aluminate solutions with the oxides or hydroxides of calcium or magnesium.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=>

(FILE 'HOME' ENTERED AT 11:04:42 ON 03 JUL 2003)

FILE 'USPATFULL' ENTERED AT 11:05:37 ON 03 JUL 2003

L1	1531 S CLATHRATE
L2	302 S L1 AND PHENOL
L3	235 S L2 AND DERIVATIVE
L4	70 S L3 AND CLATHRATE COMPOUND
L5	12 S L4 AND HOST
L6	12 DUP REM L5 (0 DUPLICATES REMOVED)
L7	21 S CLATHRATE COMPOUND/TI
L8	8 S L7 AND PHENOL
L9	0 S L8 AND PHENOL DERIVATIVE
L10	0 S L8 AND PHENOL HOST
L11	0 S L8 AND REACTING A PHENOL
L12	0 S L8 AND REACTING PHENOL
L13	0 S L8 AND ANTIBACTERI?
L14	1 S L8 AND ?BACTER?